

Day : Tuesday
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Inventor Name Search Result

Your Search was:

Last Name = MIEHER

First Name = WALTER

Application#	Patent#	Status	Date Filed	Title	Inventor Name 33
<u>60504093</u>	Not Issued	020	09/19/2003	APPARATUS AND METHODS FOR DETECTING OVERLAY ERRORS USING SCATTEROMETRY	MIEHER, WALTER D.
<u>60498524</u>	Not Issued	020	08/27/2003	METHOD AND APPARATUS COMBINING IMAGING AND SCATTEROMETRY FOR OVERLAY METROLOGY	MIEHER, WALTER
<u>60449496</u>	Not Issued	020	02/22/2003	METHOD AND SYSTEM FOR DETERMINING OVERLAY ERRORS BASED ON SCATTEROMETRY SIGNALS ACQUIRED FROM MULTIPLE OVERLAY MEASUREMENT PATTERNS	MIEHER, WALTER DEAN
<u>60441077</u>	Not Issued	020	01/17/2003	METHOD FOR DETERMINING OVERLAY ERROR BY COMPARISON BETWEEN 2 OR MORE MEASURED SCATTEROMETRY SIGNALS	MIEHER, WALTER DEAN
<u>60441048</u>	Not Issued	020	01/17/2003	METHOD FOR PROCESS OPTIMIZATION AND CONTROL BY COMPARISON BETWEEN 2 OR MORE MEASURED SCATTEROMETRY SIGNALS	MIEHER, WALTER DEAN
<u>60440970</u>	Not Issued	020	01/17/2003	METHOD FOR DETERMINING OVERLAY ERROR BY COMPARISON BETWEEN SCATTEROMETRY SIGNALS FROM MULTIPLE OVERLAY MEASUREMENT TARGETS WITH SPECTROSCOPIC IMAGING OR SPECTROSCOPIC SCANNING	MIEHER, WALTER DEAN

				APPARATUS	
<u>60431314</u>	Not Issued	020	12/05/2002	METHOD FOR DETERMINING OVERLAY ERROR BY COMPARISON BETWEEN SCATTEROMETRY SIGNALS FROM MULTIPLE OVERLAY MEASUREMENT TARGETS	MIEHER, WALTER
<u>60391290</u>	Not Issued	159	06/24/2002	SPECTROSCOPIC CD METROLOGY FOR SUB-100NM LITHOGRAPHY PROCESS CONTROL	MIEHER, WALTER DEAN
<u>60361837</u>	Not Issued	159	03/04/2002	METHOD FOR DETERMINING LITHOGRAPHIC FOCUS USING MULTIPLE SCATTEROMETRY MEASUREMENTS	MIEHER, WALTER DEAN
<u>60343077</u>	Not Issued	159	12/19/2001	PARAMETRIC PROFILING USING OPTICAL SPECTROSCOPIC SYSTEMS	MIEHER, WALTER
<u>60338204</u>	Not Issued	159	11/09/2001	FOCUS MASKING STRUCTURES, FOCUS PATTERNS AND MEASUREMENTS THEREOF	MIEHER, WALTER DEAN
<u>60301763</u>	Not Issued	159	06/27/2001	OVERLAY MARKS, METHOD OF OVERLAY MARK DESIGNED AND METHODS OF OVERLAY MEASUREMENTS	MIEHER, WALTER DEAN
<u>60301591</u>	Not Issued	159	06/27/2001	OVERLAY MARKS, METHOD OF OVERLAY MARK DESIGNED AND METHODS OF OVERLAY MEASUREMENTS	MIEHER, WALTER DEAN
<u>60301484</u>	Not Issued	159	06/27/2001	OVERLAY MARKS, METHOD OF OVERLAY MARK DESIGNED AND METHODS OF OVERLAY MEASUREMENTS	MIEHER, WALTER DEAN
<u>60301270</u>	Not Issued	159	06/26/2001	METHOD FOR DETERMINING LITHOGRAPHIC FOCUS	MIEHER, WALTER DEAN
<u>60229256</u>	Not Issued	159	08/30/2000	IMAGING TECHNIQUE FOR OVERLAY ALIGNMENT MARKS	MIEHER, WALTER DEAN
<u>10785821</u>	Not Issued	019	02/23/2004	APPARATUS AND METHODS FOR DETECTING OVERLAY ERRORS USING SCATTEROMETRY	MIEHER, WALTER D.
<u>10785732</u>	Not Issued	019	02/23/2004	APPARATUS AND METHODS FOR DETECTING OVERLAY	MIEHER, WALTER D.

				ERRORS USING SCATTEROMETRY	
<u>10785731</u>	Not Issued	019	02/23/2004	APPARATUS AND METHODS FOR DETECTING OVERLAY ERRORS USING SCATTEROMETRY	MIEHER, WALTER D.
<u>10785723</u>	Not Issued	019	02/23/2004	APPARATUS AND METHODS FOR DETECTING OVERLAY ERRORS USING SCATTEROMETRY	MIEHER, WALTER D.
<u>10785430</u>	Not Issued	019	02/23/2004	APPARATUS AND METHODS FOR DETECTING OVERLAY ERRORS USING SCATTEROMETRY	MIEHER, WALTER D.
<u>10785396</u>	Not Issued	019	02/23/2004	APPARATUS AND METHODS FOR DETECTING OVERLAY ERRORS USING SCATTEROMETRY	MIEHER, WALTER D.
<u>10785395</u>	Not Issued	019	02/23/2004	APPARATUS AND METHODS FOR DETECTING OVERLAY ERRORS	MIEHER, WALTER D.
<u>10760149</u>	Not Issued	019	01/17/2004	METHOD FOR PROCESS OPTIMIZATION AND CONTROL BY COMPARISON BETWEEN 2 OR MORE MEASURED SCATTEROMETRY SIGNALS	MIEHER, WALTER
<u>10729838</u>	Not Issued	018	12/05/2003	APPARATUS AND METHOD FOR DETECTING OVERLAY ERRORS USING SCATTEROMETRY	MIEHER, WALTER D.
<u>10327466</u>	Not Issued	020	12/19/2002	PARAMETRIC PROFILING USING OPTICAL SPECTROSCOPIC SYSTEMS	MIEHER, WALTER
<u>10291181</u>	Not Issued	030	11/07/2002	FOCUS MASKING STRUCTURES, FOCUS PATTERNS AND MEASUREMENTS THEREOF	MIEHER, WALTER DEAN
<u>10186324</u>	Not Issued	030	06/26/2002	OVERLAY MARKS, METHODS OF OVERLAY MARK DESIGN AND METHODS OF OVERLAY MEASUREMENTS	MIEHER, WALTER DEAN
<u>10186294</u>	Not Issued	030	06/26/2002	METHOD FOR DETERMINING LITHOGRAPHIC FOCUS AND EXPOSURE	MIEHER, WALTER
<u>10184026</u>	Not	030	06/26/2002	OVERLAY MARKS, METHODS	MIEHER, WALTER

	Issued			OF OVERLAY MARK DESIGN AND METHODS OF OVERLAY MEASUREMENTS	DEAN
<u>10184013</u>	Not Issued	030	06/26/2002	OVERLAY MARKS, METHODS OF OVERLAY MARK DESIGN AND METHODS OF OVERLAY MEASUREMENTS	MIEHER, WALTER DEAN
<u>09894987</u>	Not Issued	030	06/27/2001	OVERLAY MARKS, METHODS OF OVERLAY MARK DESIGN AND METHODS OF OVERLAY MEASUREMENTS	MIEHER, WALTER DEAN
<u>09654318</u>	<u>6486954</u>	150	09/01/2000	OVERLAY ALIGNMENT MEASUREMENT MARK	MIEHER, WALTER DEAN

Inventor Search Completed: No Records to Display.

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